

Co-doped Ni hydroxide and oxide nanosheet networks: Laser-Assisted Synthesis, Effective Doping, and Ultrahigh Pseudocapacitor

Performance

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1. Preparation of pure Ni(OH)₂ nanosheet network

Pure Ni(OH)₂ nanosheet network was synthesized using a LAL technique. In a typical process, a nickel metal plate (99.99% purity) was fixed on a supporter in a vessel that filled with 15 mL 0.2 M Na₂S₂O₃ solution. Upon ablation of the metal plate, the vessel was rotated (10 rpm) by a motorized tunable stage. The metal plate was ablated using a Nd:YAG pulsed laser at 1064 nm wavelength with an energy density of 130 mJ per pulse and a pulse duration of 10 ns. After ablation for 20 min, the suspension was stored in a container and aged at room temperature for 1 week. After sufficient growth, the obtained gray-color precipitates were collected and dried in a vacuum chamber at 50 °C overnight (Fig. S1).

2. Characterization of pure Ni(OH)₂ nanosheet

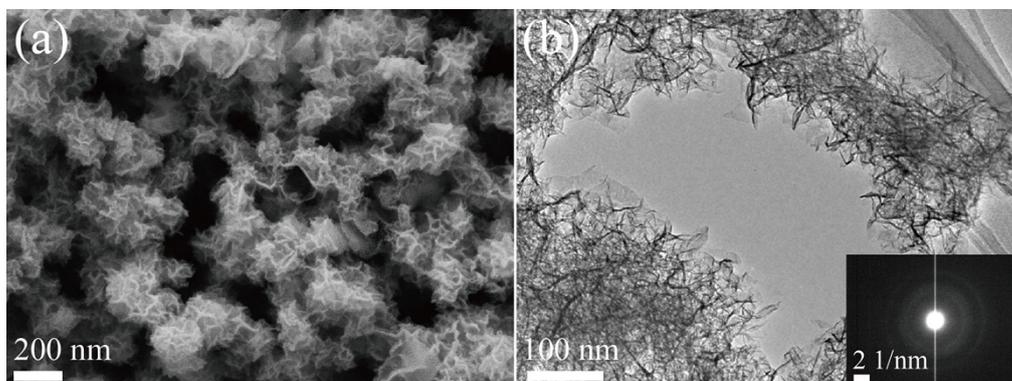


Fig. S1. (a) FESEM image, (b) TEM image and corresponding SAED pattern (inset) of pure Ni(OH)₂. The morphology of pure Ni(OH)₂ is very similar to CN-0.1, both of them are composed of nanosheet network. The diffused halo of the selected-area electron diffraction (SAED) pattern in the inset of Figure S1(b) also indicates the poor crystallinity and polycrystalline characteristics of the sample.^[1]

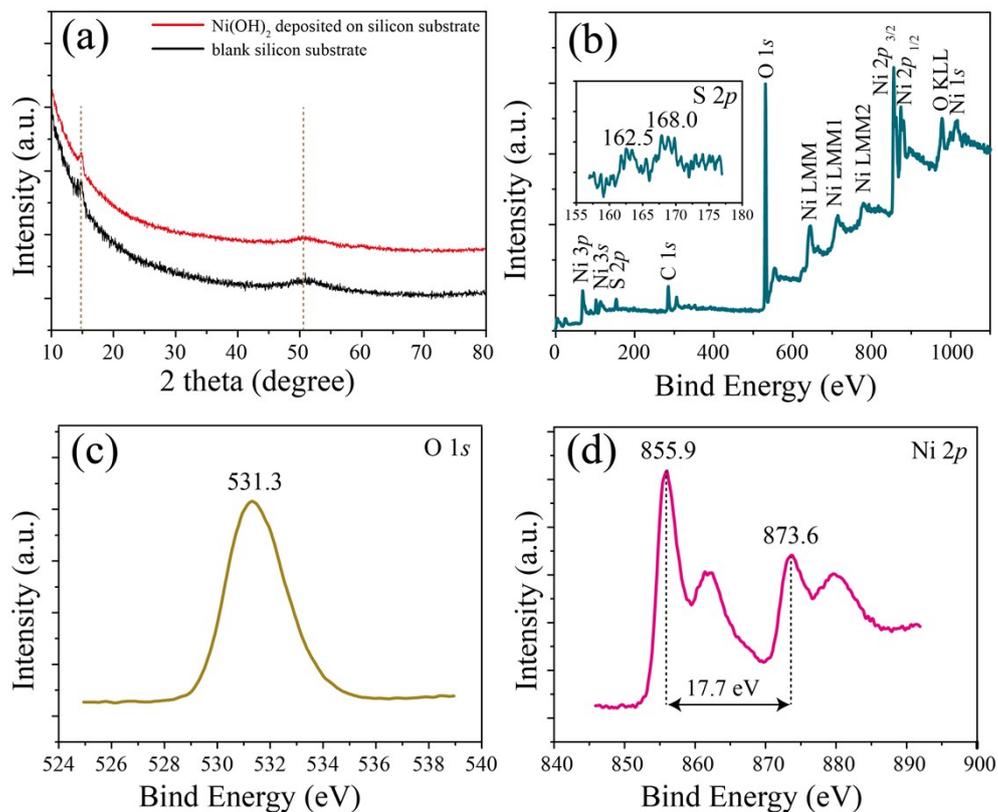


Fig. S2. (a) XRD spectra and (b) the survey XPS spectrum of pure Ni(OH)₂, and high-resolution spectra of (c) O 1s, (d) Ni 2p. As demonstrated by XRD measurement, the curve of the product shows no obvious sharp peak, indicating its amorphous structure. According to the *Handbook of X-ray Photoelectron Spectroscopy*, the S peak inset of Fig. S2(b) can be associated with the S 2p from the intercalated SO₄²⁻ group between the Ni(OH)₂ layers or the adsorbed S₂O₃²⁻ on the surface. The binding energy of 531.3 eV for O 1s can be mainly derived from the hydroxyl group (O-H) with a binding energy of ~531 eV [Fig. S2(c)]. Fig. S2(d) exhibits the high-resolution Ni 2p_{3/2} and Ni 2p_{1/2} peaks centered at 855.7 and 873.6 eV respectively, with a spin-energy separation of 17.9 eV, which is in good agreement with reported data for Ni²⁺. These results together demonstrate the product is amorphous Ni(OH)₂.

3. Additional characterization of CN-0.1 and CN-0.2

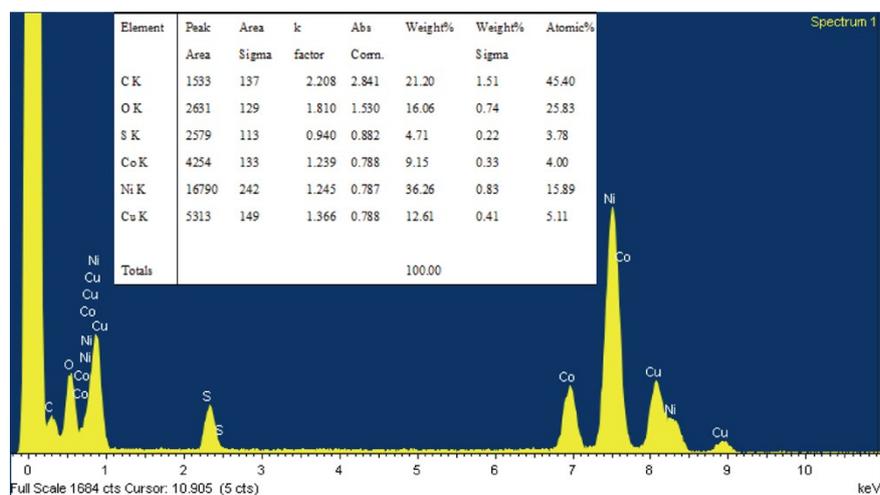


Fig. S3. EDX spectrum of sample CN-0.1. From the picture, we can see that the atomic ratio of the Co and Ni is approximately equal to 1:4.

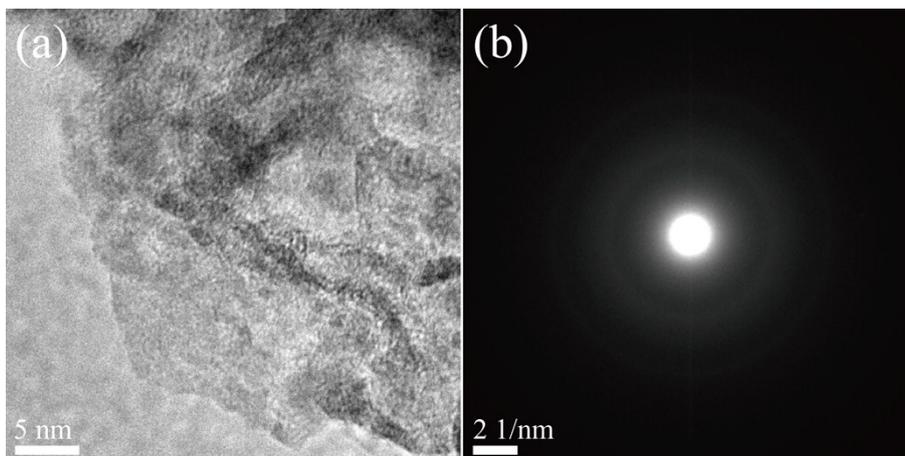


Fig. S4. (a) HRTEM image and (b) SAED pattern of sample CN-0.2. No obvious lattice fringe can be found in the HRTEM image, together with the diffused halo of the selected-area electron diffraction (SAED) pattern, these results suggest that the products synthesized in this way tend to be a low crystalline or amorphous structure.

4. Electrochemical test of pure Ni(OH)₂

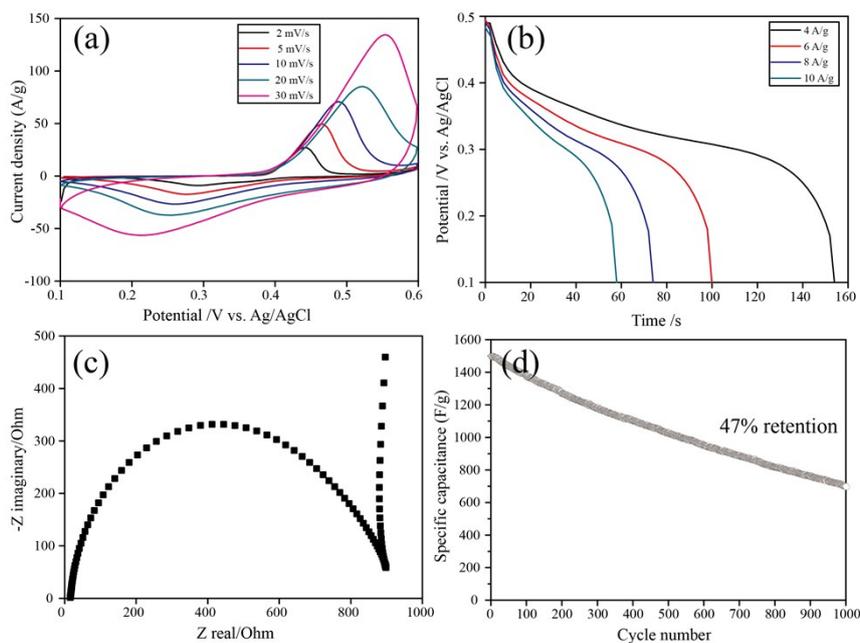


Fig. S5. (a) CV curves of pure Ni(OH)₂ at scan rate of 2, 5, 10, 20 and 30 mV/s; (b) galvanostatic discharging curve of pure Ni(OH)₂ at current densities of 4, 6, 8 and 10 A/g; (c) Nyquist plots of pure Ni(OH)₂; (d) cycling performance of pure Ni(OH)₂ at a discharge current density of 6 A/g. Cyclic voltammetry (CV), electrochemical impedance spectroscopy (EIS) and galvanostatic charge/discharge measurements were conducted in 1 M KOH solution.

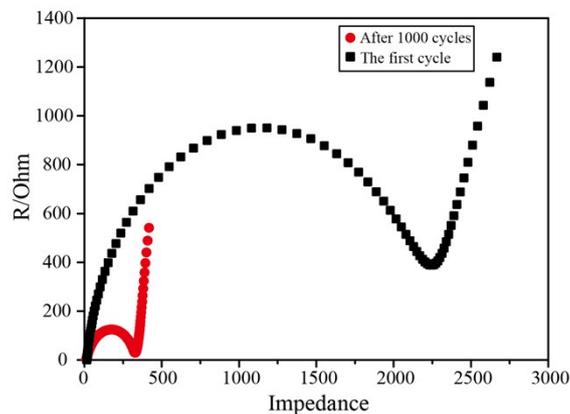


Fig. S6. Nyquist plots of the sample CN-0.2 before and after 1000 cycles.

References

- [1] Wang, C. H.; Zhang, X.; Xu, Z. T. Ethylene Glycol Intercalated Cobalt/Nickel Layered Double Hydroxide Nanosheet Assemblies with Ultrahigh Specific Capacitance: Structural Design and Green Synthesis for Advanced Electrochemical Storage. *ACS Appl. Mater. Interfaces* 2015, 7, 19601-19610.